EL799949505

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. M122-2297	SERIAL NO. Filed Herewith
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Garo J. Derderian et al.	
		FILING DATE Filed Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,444,495 B1	09/02	Leung et al.			

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

	AB	Frank, M. et al., "Enhanced Initial Growth of Atomic-Layer-Deposited Metal Oxides on Hydrogen-Terminated Silicon", App. Phys. Let., Vol. 83, No. 4, July 28, 2003, pp. 740-742.
	AC	Rosidian, A.. et al., "Formation of Ultrahard Metal Oxide Nanocluster Coatings at Room Temperature by Electrostatic Self-Assembly", SPIE Vol. 3675 (1999), pp. 113-119.
	AD	Sakaue, H. et al., "Conformable CVD of SiO_2 into Deep Trench Using the Digital Method", Extended Abstracts of the 22nd (1990 International) Conf. on Solid State Devices and Materials, Sendai (1990), pp. 921-924.
	AE	Mountziaris, T. et al., "Gas-Phase and Surface Chemistry in Electronic Materials Processing", Materials Research Society Symposium Proceedings, Vol. 334, held 11/29/93 - 12/2/93, Boston, MA, pp. 1-36.
	AF	Perez, I. et al., "Fabrication and Characterization of 4H-SiC MOS Capacitors with Atomic Layer Deposited (ALD) SiO_2", IEEE 7/00, pp. 144-147.
	AG	Sakaue, H. et al., "Digital Chemical Vapor Deposition of SiO_2 Using a Repetitive Reaction of Triethylsilane/Hydrogen and Oxidation", JP Journal of Appl. Phys., Vol. 70, No. 1B, Jan. 1991, pp. L 124-L 127.
	AH	Klaus, J. et al., "Atomic Layer Deposition of SiO_2 at Room Temperature Using NH_3-Catalyzed Sequential Surface Reactions", Surface Science 447 (2000), pp. 81-90.
	AI	Cameron, M. et al., "Atomic Layer Deposition of SiO_2 and TiO_2 in Alumina Tubular Membranes: Pore Reduction and Effect of Surface Species on Gas Transport", Langmuir 2000, 16, pp. 7435-7444.
	AJ	Horiike, Y. et al., "Filling of Si Oxide into a Deep Trench Using Digital CVD Method", App. Surface Science 46, (1990), pp. 168-174.
	AK	Wise, M. et al., "Diethyldiethoxysilane as a New Precursor for SiO_2 Growth on Silicon", Mat. Res. Soc. Symp. Proc. Vol. 334, (©1994 Materials Research Society), pp. 37-43.

EXAMINER	/Matthew Such/	DATE CONSIDERED	06/19/2006

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

EL979949505

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. M122-2297	SERIAL NO. Filed Herewith
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Garo J. Derderian et al.	
		FILING DATE Filed Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	US2003/ 0026989 A1	Pub. 2/6/03	George et al.			07/16/02
	AB	US2002/ 0137260 A1	Pub. 9/26/02	Leung et al.			01/11/01
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR		
	AS		
	AT		

EXAMINER	/Matthew Such/	DATE CONSIDERED	06/19/2006

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-1449U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

ATTY. DOCKET NO.	SERIAL NO.
MI22-2297	10/728,328
APPLICANT: Garo J. Derderian et al.	
FILING DATE: December 1, 2003	GROUP: Unknown

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR		Klaus, J.W. et al., "Atomic Layer Deposition of SiO_2 Using Catalyzed and Uncatalyzed Self-Limiting Surface Reactions", Surface Review and Letters, Vol. 6, Nos. 3 & 4 (1999), © World Scientific Pub. Co., pp. 435-448.
	AS		

EXAMINER /Matthew Such/ DATE CONSIDERED 06/19/2006

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.